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PATENT  
DKT. NO.: 29273/502

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS : Hajime KAWANO, et al.  
SERIAL NO. : 09/315,988  
FILED : May 21, 1999  
FOR : ELECTRON BEAM LITHOGRAPHY SYSTEM  
GROUP ART : 2881  
EXAMINER : Kalimah Fernandez

Assistant Commissioner for Patents  
Washington D.C. 20231

RECEIVED  
NOV 18 2002  
TECHNOLOGY CENTER 2800

AMENDMENT

Sir:

In response to the office action dated May 22, 2002, the due date being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS

Please amend claim 1 as follows:

1. (Amended) An electron beam lithograph system comprising:  
exposure map creating means which, based on positional relations between meshes  
dividing a region to be rendered by an electron beam on the one hand and shots to be rendered by  
said electron beam on the other hand, creates an exposure map by calculating an area density  
from a shot area included in each of said meshes; and  
proximity effect correcting means for correcting a level of exposure for each of said shots  
by referencing said exposure map so that each shot is exposed at the corrected level;  
wherein said exposure map creating means includes judging means for judging whether  
or not each shot straddles a plurality of meshes by using a plurality of memories and adding  
circuits.